Notice of Allowability	Application No.	Applicant(s)
	10/080,540	MIZUMURA ET AL.
	Examiner	Art Unit
	Shamim Ahmed	1765
The MAILING DATE of this communication appeal of the communication appeal claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communication GHTS. This application is subject	oplication. If not included on will be mailed in due course. THIS
1. $\boxtimes$ This communication is responsive to <u>12/29/03</u> .		
2. ⊠ The allowed claim(s) is/are <u>10-23</u> .		
3. $igotimes$ The drawings filed on <u>25 February 2002</u> are accepted by the	ne Examiner.	
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority ur</li> <li>a)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority do</li> <li>International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul>	e been received. e been received in Application No. cuments have been received in this	s national stage application from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a repl IENT of this application.	y complying with the requirements
<ol> <li>A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give</li> </ol>	itted. Note the attached EXAMINE es reason(s) why the oath or declar	R'S AMENDMENT or NOTICE OF ration is deficient.
<ol> <li>CORRECTED DRAWINGS (as "replacement sheets") muse (a) ☐ including changes required by the Notice of Draftspers 1) ☐ hereto or 2) ☐ to Paper No./Mail Date</li> <li>(b) ☐ including changes required by the attached Examiner' Paper No./Mail Date</li> <li>Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the state of the sheet in the same of the sheet in the same of the sheet in the same of the same</li></ol>	son's Patent Drawing Review(PTC . s Amendment / Comment or in the .84(c)) should be written on the draw	Office action of rings in the front (not the back) of
<ol> <li>DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT</li> </ol>	sit of BIOLOGICAL MATERIAL FOR THE DEPOSIT OF BIOLOGIO	must be submitted. Note the CAL MATERIAL.
	1	
Attachment(s)	E □ Notice of Informati	Patent Application (PTO-152)
1. Notice of References Cited (PTO-892)	5. ∐ Notice of Informal 6. ⊠ Interview Summar	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	Paper No./Mail D	
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date</li> </ol>		
4.   Examiner's Comment Regarding Requirement for Deposit		nent of Reasons for Allowance
of Biological Material	9.	
		NADINE G. NORTON VISORY PATENT EXAMINER

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## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Alan E. Schiavelli on 4/1/14.

The application has been amended as follows:

IN THE SPECIFICATION:

At page 12, line 5, replace "Figure 4 is a" with "Figures 4a-4f are".

At page 39, replace the "Abstract of the Disclosure" with the following paragraph:

"This invention relates to a method for etching an organic insulating film used in the production of semiconductor devices. A sample to be etched on which a low dielectric constant organic insulating film is formed and is etched by generating a plasma from hydrogen gas and nitrogen gas or ammonia gas, and controlling the gas flow rate and pressure so that the light emission spectral intensity ratio of hydrogen atom and cyan molecule in the plasma comes to a prescribed value. By this method, a low dielectric constant organic insulating film as an insulating film between layers can be etched without using any etch stop layer so that bottom surface of trenches and holes for electrical wiring become flat."

IN THE CLAIMS:

Cancel claims 1-9.

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- 2. The following is an examiner's statement of reasons for allowance: The prior art does not teach a process for etching an organic insulating film to a prescribed depth while suppressing microtrenching, wherein the etching is performed without using an etching stopper layer and the prescribed depth is less than the thickness of the organic insulating film as the context of claim 10.
- 3. The closest prior art Fukazawa (JP-2000-252359) discloses a process for etching an organic insulating film until the wiring layer is exposed but fails to teach etching a portion of the organic insulating film to a prescribed depth, which depth is less than the thickness of the organic insulating film.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shamim Ahmed whose telephone number is (571) 272-1457. The examiner can normally be reached on M-Thu (7:00-5:30) Every Friday Off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Shamim Ahmed Examiner Art Unit 1765

SA Thursday, April 01, 2004

> NADINE G. NORTON SUPERVISORY PATENT EXAMINER

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